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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 1

Complete if Known

Application Number 09/422,398
Filing Date October 21, 1999
First Named Inventor Bruce W. Smith
Group Art Unit Unknown 285/
Examiner Name Unknown
Attorney Docket Number 88405.99R077

U.S. PATENT DOCUMENTS

Examiner Initials ¹	Cite No. ¹	U.S. Patent Document Number	Kind Code ² (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
HN	1	5,627,625		Tohru Ogawa	05/06/97	
	2	5,638,211		Naomasa Shiraishi	06/10/97	
	3	3,776,633		Albert Frosch, et al	12/04/73	
	4	3,729,252		Clarence N. Nelson	04/24/73	
	5	5,926,257		Satoru Mizouchi	07/20/99	
	6	5,631,721		Stuart Stanton, et al.	03/20/97	5/11/1
	7	5,673,102		Akiyoshi Suzuki, et al.	09/30/97	
HN	8	5,305,054		Akiyoshi Suzuki, et al.	04/19/94	

FOREIGN PATENT DOCUMENTS

Examiner Initials ¹	Cite No. ¹	Foreign Patent Document Office ³	Number ⁴	Kind Code ⁵ (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
HN	9	EP	0 503 472 A3	EP	Minori Noguchi	09/16/92		
	10	EP	0 500 393 B1	EP	Akiyoshi Suzuki, et al.	08/26/92		
	11	EP	0 500 393 A3	EP	Akiyoshi Suzuki, et al.	08/26/92		
	12	EP	0 486 316 A3	EP	Naomasa Shiraishi	05/20/92		
	13	EP	0 496 891 A1	EP	Naomasa Shiraishi	08/05/92		
HN	14	EP	0 783 135 A1	EP	Akiyoshi Suzuki, et al.	07/09/97		

Examiner
Signature

Nguyen, Hung Henry

Date
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**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

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Filing Date	October 21, 1999
First Named Inventor	Bruce W. Smith
Group Art Unit	Unknown 2851
Examiner Name	Unknown
Attorney Docket Number	88405.99R077

Sheet 2 of 2

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.

Examiner Initials	Page No.	Other Prior Art	T ²
HN	15	S. Asai, et al., "High Performance Optical Lithography Using a Separated Light Source", <u>J. Vac. Sci. Technology</u> , Vol B 10(6), pp. 3023-3026, (November/December 1992).	
HN	16	E. Tamechika, et al., "Investigation of Single Sideband Optical Lithography Using Oblique Incidence Illumination", <u>J. Vac. Sci. Technology</u> , Vol. B 10(6), pp. 3027-3031, (November/December 1992).	
HN	17	W.N. Partlow, et al., "Depth of Focus and Resolution Enhancement for i-line and Deep-UV Lithography Using Annular Illumination", <u>SPIE Optical/Laser Microlithography</u> , Vol. 1927, pp. 137-156, (1993).	
HN	18	T. Ogawa, et al., "The Effective Light Source Optimization With the Modified Beam For the Depth-of-Focus Enhancements", <u>SPIE Optical Laser Microlithography</u> , Vol. 2197, pp. 19-30, (1994).	
HN	19	T. Ogawa, et al., "Sub-Quarter Micron Optical Lithography With Practical Super Resolution Technique", <u>SPIE Optical Laser Microlithography VIII</u> , Vol. 2440, pp. 772-783, (1995).	
HN	20	B. W. Smith, et al., "Illumination Pupil Filtering Using Modified Quadrupole Apertures", <u>SPIE Optical Microlithography XI</u> , Vol. 3334, pp. 37-47, (1998).	
HN	21	B.W. Smith, et al., "Influences of Off-Axis Illumination on Optical Lens Aberration", <u>J. Vac. Sci. Technology</u> , Vol. B16(6) 3398, pp. 3405-3410, (November/December 1998).	
HN	22	Chin C. Hsia, et al., "Customized Off-Axis Illumination Aperture Filtering for Sub 0.18 um KrF Lithography", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 39-46, (1999).	
HN	23	P. Zandbergen, et al., "Optical Extension at the 193nm Wavelength", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 29-38, (1999).	
HN	24	Z. Yang, et al., "Corrections of Aberrations Using HOE's in UV and Visible Imaging Systems", <u>SPIE International Lens Design Conference</u> , Vol. 1354, pp. 323-327, (1990).	
HN	25	B. W. Smith, <u>Microlithography: Science and Technology</u> , Chapter 3, New York: Marcel Dekker (1998), pp. 216-231.	

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